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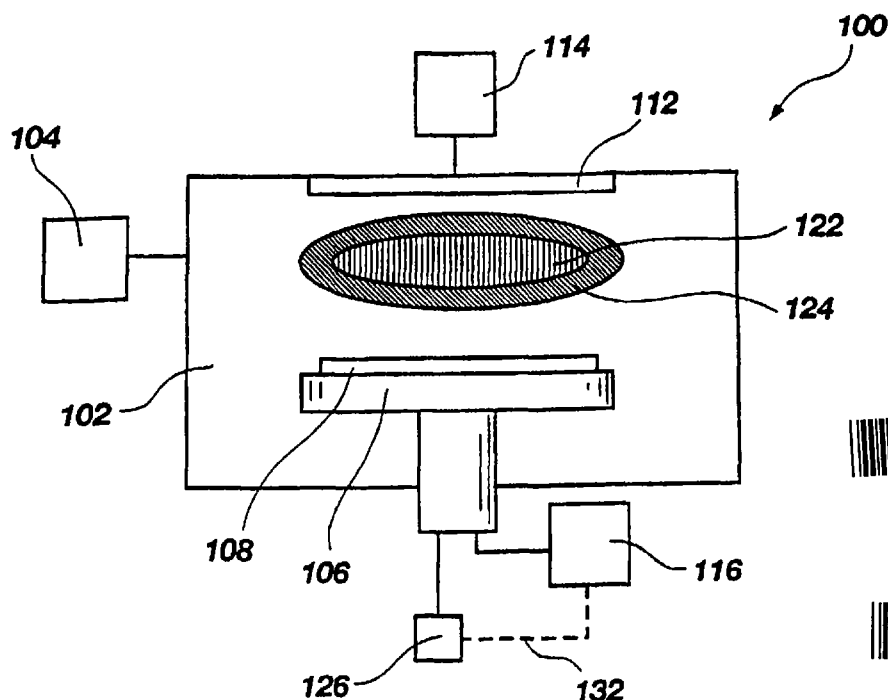
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(54) Title: **USE OF PULSED VOLTAGE IN A PLASMA REACTOR**



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(57) Abstract: A method and apparatus for providing a positive voltage spike to a semiconductor substrate pedestal during a portion of a high voltage power bias oscillation cycle to reduce or eliminate the detrimental effects of feature charging during the operation of a plasma reactor.

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